

	Type	Ref #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
1	BRS	S10	251	etch\$3 same (nitride or "TiN" or "silicon nitride" or "titanium nitride" or "tantalum nitride" or TaN or SiN or Si3N4 or "Si.sub.3N.sub.4") same ((photoresist or resist or mask\$3) with (("193" or "193 nm") and ("248" or "248 nm"))))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TD B	2006/02/10 11:08			
2	BRS	S31	2	"20040171260"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TD B	2006/02/13 17:22			
3	BRS	S32	11068	etch\$3 same (ARC or ARL or OARC or BARAC or (antireflect\$3 with (layer or coat\$3 or material)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TD B	2006/02/13 17:45			
4	BRS	S33	9	S32 same (("CO" or "carbon dioxide") and (CHF3 or "CHF.sub.3" or "triflouro methane" or "carbon trifluoride") and (N2 or "N.sub.2" or "nitrogen") and ("H.sub.2" or H2 or "hydrogen"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TD B	2006/02/13 17:53			

5	BRS	S34	14	S32 same (("CO" or "carbon dioxide") and (CHF3 or "CHF.sub.3" or "trifluoro methane" or "carbon trifluoride") and (N2 or "N.sub.2" or "nitrogen") and ((CF4 or "C.sub.4" or "tetra fluoro methane" or "carbon tetrafluoride") or ("H.sub.2" or H2 or "hydrogen"))))	US-PGPUB; USPAT; USOCR ; EPO; JPO; DERWE NT; IBM_TD B	2006/02/13 18:11			
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	Type	Ref #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
6	BRS	S35	105	etch\$3 same (ARC or ARL or OARC or BARC or (antireflect\$3 with (layer or coat\$3 or material))) same (("193 nm" or "193") with (photoresist or resist or mask\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:07			
7	BRS	S36	0	S35 same (("CO" or "carbon dioxide") and (CHF3 or "CHF.sub.3" or "triflouro methane" or "carbon trifluoride") and (N2 or "N.sub.2" or "nitrogen") and ("H.sub.2" or H2 or "hydrogen"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 17:53			
8	BRS	S37	8	S35 and (("CO" or "carbon dioxide") and (CHF3 or "CHF.sub.3" or "triflouro methane" or "carbon trifluoride") and (N2 or "N.sub.2" or "nitrogen") and ("H.sub.2" or H2 or "hydrogen"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:19			
9	BRS	S38	10	S35 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:22			

10	BRS	S39	106	etch\$3 same (ARC or ARL or OARC or BARC or OARL or BARL or OARC or (organic adj antireflect\$3) or (antireflect\$3 with (layer or coat\$3 or material))) same (("193 nm" or "193") with (photoresist or resist or mask\$3))	US-PGPUB; USPAT; USOCR ; EPO; JPO; DERWE NT; IBM_TD B	2006/02/13 18:10			
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	Type	Ref #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
11	BRS	S40	0	S39 same (("CO" or "carbon dioxide") and (CHF3 or "CHF.sub.3" or "trifluoro methane" or "carbon trifluoride") and (N2 or "N.sub.2" or "nitrogen") and ((CF4 or "C.sub.4" or "tetra fluoro methane" or "carbon tetrafluoride") or ("H.sub.2" or H2 or "hydrogen"))))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:11			
12	BRS	S42	1	S41 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:12			
13	BRS	S41	8	S39 and (("CO" or "carbon dioxide") and (CHF3 or "CHF.sub.3" or "trifluoro methane" or "carbon trifluoride") and (N2 or "N.sub.2" or "nitrogen") and ((CF4 or "C.sub.4" or "tetra fluoro methane" or "carbon tetrafluoride") or ("H.sub.2" or H2 or "hydrogen"))))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:13			
14	BRS	S43	5	S35 and (("CO" or "carbon dioxide") and (CHF3 or "CHF.sub.3" or "trifluoro methane" or "carbon trifluoride") and (N2 or "N.sub.2" or "nitrogen") and ("H.sub.2" or H2 or "hydrogen")) and sccm	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:21			

15	BRS	S44	63	etch\$3 same (plasma or rie) same ((conventional or known) with (flowrate or sccm))	US- PGPUB; USPAT; USOCR ; EPO; JPO; DERWE NT; IBM_TD B	2006/02/1 3 18:22			
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	Type	Ref #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
16	BRS	S45	36	S44 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; ; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:31			
17	BRS	S46	1	CHOI-YOUNGJIN.in.	US-PGPUB; USPAT; USOCR; ; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:31			
18	BRS	S47	16	ZHU-HELEN-H.in.	US-PGPUB; USPAT; USOCR; ; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:34			
19	BRS	S48	4	LEE-SANGHEON.in.	US-PGPUB; USPAT; USOCR; ; EPO; JPO; DERWE NT; IBM_TDB	2006/02/13 18:34			

20	BRS	S49	12	KANG-SEAN-S.in.	US- PGPUB; USPAT; USOCR ; EPO; JPO; DERWE NT; IBM_TD B	2006/02/1 3 18:35			
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	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
1	BRS	L1	1161	((stop\$4 or halt\$3 or ceas\$3) with etch\$3) same (ARC or antireflect\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 16:32			
2	BRS	L2	672	((stop\$4 or halt\$3 or ceas\$3) with etch\$3) with (ARC or antireflect\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 16:36			
3	BRS	L3	617	2 and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 16:37			
4	BRS	L4	219	3 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 16:37			
5	BRS	L5	229	((stop\$4 or halt\$3 or ceas\$3) adj3 etch\$3) same (ARC or antireflect\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 16:37			
6	BRS	L6	103	((stop\$4 or halt\$3 or ceas\$3) adj3 etch\$3) with (ARC or antireflect\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 16:37			
7	BRS	L7	99	6 and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 16:37			
8	BRS	L8	37	7 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 17:39			

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
9	BRS	L9	0	8 not (etch\$3 stop\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 17:36			
10	BRS	L10	353	etch\$3 with ("CO" or "carbon monoxide") with sccm	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 17:37			
11	BRS	L11	14	(etch\$3 with ("CO" or "carbon monoxide") with sccm) same (ARC or ARL or OARC or OARL or BARC or antireflect\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 18:27			
12	BRS	L12	5	11 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 17:41			
13	BRS	L13	137	10 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 18:46			
14	BRS	L14	111	etch\$3 same ((photoresist or resist or mask) with ("193 nm" or "193")) same (ARC or ARL or OARC or OARL or BARC or antireflect\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 18:29			
15	BRS	L15	10	14 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:02			
16	BRS	L17	1	16 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:08			

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
17	BRS	L16	28	(seed with silicon) same (SiGe or "silicon germanium") same ("nm" or nanometer or nanometre)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:08			
18	BRS	L18	98	(seed with silicon) same (SiGe or "silicon germanium") same ("nm" or nanometer or nanometre or thickness of size or length)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:15			
19	BRS	L19	37	18 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:22			
20	BRS	L20	36	19 not 16	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:23			
21	BRS	L21	101	(seed with silicon) same (SiGe or "silicon germanium") same ("nm" or nanometer or nanometre or thickness or "mu.m" or micron or Angstrom or size or length)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:24			
22	BRS	L22	40	21 and @pd<="20020614"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:22			
23	BRS	L23	4	22 not 20	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:23			
24	BRS	L24	6	(seed adj silicon) same (SiGe or "silicon germanium") same ("nm" or nanometer or nanometre or thickness or "mu.m" or micron or Angstrom or size or length)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:46			

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
25	BRS	L25	1	CHOI-YOUNGJIN.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:46			
26	BRS	L26	16	ZHU-HELEN-H.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:48			
27	BRS	L27	4	LEE-SANGHEON.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:50			
28	BRS	L28	12	KANG-SEAN-S.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/28 20:50			